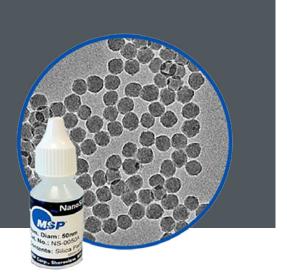


NanoSilica™ Size Standards



Concentrated aqueous suspensions of SiO₂ particles with highly uniform size distributions

NanoSilica™ Size Standards from MSP, a Division of TSI®, are ideally suited for producing high-quality calibration standards for the next generation of wafer and photomask inspection systems. They are available in nominal sizes ranging from 15 to 200 nm.

Applications

- Wafer and reticle (photomask) inspection tool calibration
- Inspection tool development and qualification
- Incoming bare wafer inspection/qualification
- Blanket film monitoring
- Incoming reticle (photomask) inspection/qualification
- Production reticle (photomask) monitoring
- Process tool qualification and monitoring
- Particle counter calibration

Benefits

- Easily discern modal (peak) diameter
- Avoid discrepancies due to differences between mean and peak diameter values
- Prepare diluted suspensions suitable for aerosol generation devices with relatively high or low efficiencies
- Create long-lasting calibration standards for state-of-the-art inspection tools
- Consume less material; save money
- Comes with a Certificate of Calibration and Traceability and a Safety Data Sheet (SDS) with handling and disposal instructions

Features

- Extremely uniform size distribution
 Manufactured with a patented SiO₂ synthesis process, our NanoSilica™ Size Standards have size distributions narrower than commercially available PSL spheres.
- Peak diameter measured with SI traceability
 Allows yield-enhancement and metrology groups to establish traceability of their inspection and defect review methods in accordance with ISO 9000 standards and SEMI guidelines.
- Stable when subjected to intense DUV radiation MSP's SiO₂ particles will not degrade when exposed to DUV radiation, unlike PSL spheres, which can decrease in size.
- Easy to use

NanoSilica particle suspensions are available in droppertip bottles for convenience when mixing suspensions with appropriate number concentrations for your applications.

High particle concentration
 Some applications require high number concentrations.
 MSP's particle concentrations are one of the highest in the industry.

Nanosilica[™] Size Standards



Standard Offerings

Other sizes may be available upon request. Please contact MSP™ for more information.

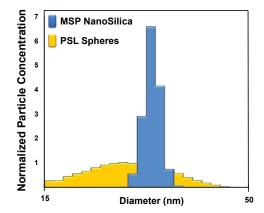
Model (Starting with 2260-02-)	Catalog Number	Nominal Particle Diameter [nm]	Certified ¹ Peak Diameter [nm]	Approx. Size Dist. Width, RFWHM ²
1044	NS-0015A	15	14-16	13%
1046	NS-0018A	18	17-19	12%
1047	NS-0020A	20	19-21	11%
1073	NS-0022A	22	21-23	11%
1048	NS-0024A	24	23-25	10%
1074	NS-0026A	26	25-27	9%
1075	NS-0027A	27	26-28	9%
1049	NS-0030A	30	29-31	8%
1079	NS-0032A	32	31-33	7%
1062	NS-0035A	35	34-36	7%
1076	NS-0037A	37	36-38	6%
1051	NS-0040A	40	39-41	6%
1063	NS-0045A	45	44-46	5%
1052	NS-0050A	50	49-51	5%
1077	NS-0055A	55	53-57	5%
1053	NS-0060A	60	58-62	4%
1067	NS-0064A	64	62-66	4%
1054	NS-0070A	70	68-72	4%
1068	NS-0074A	74	72-76	4%
1055	NS-0080A	80	78-82	4%
1069	NS-0084A	84	82-86	4%
1057	NS-0090A	90	88-92	4%
1070	NS-0094A	94	92-96	4%
1058	NS-0100A	100	98-102	4%
1071	NS-0104A	104	102-106	4%
1059	NS-0125A	125	120-130	4%
1060	NS-0150A	150	145-155	4%
1061	NS-0200A	200	190-210	4%

Certified diameter for a given catalog number will be provided in the stated range.
 Relative FWHM (full-width at half-maximum); FWHM divided by modal diameter.

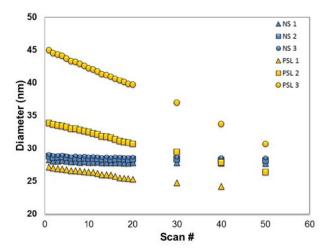
The MSP logo is a trademark of MSP Corporation. TSI and the TSI logo are registered trademarks

Specifications

Particle Composition	Amorphous SiO ₂		
Particle Density	1.9 g/cm ³		
Index of Refraction	1.41 @ 633nm		
Volume	5 mL		
Concentration	10 ¹³ to 10 ¹⁵ particles per mL		
Expiration Date	≥ 24 months		
Additives	Ethanol (5-20% by mass) Organic stabilizer (<0.1% by mass)		
Storage & Handling	Store at room temperature (See Certificate of Calibration and Traceability for more details.)		



Comparison of size distributions of a commercially available PSL size standard (30 nm) and MSP's NanoSilica $^{\text{TM}}$ (30 nm). Suspensions of particles were aerosolized with aerosol electrospray (TSI $^{\text{e}}$ Model 3480). Size distributions were measured by particle mobility spectrometry. Particle suspensions were diluted in equal volume ratios.



Comparison of NanoSilica and PSL stability under DUV laser illumination: particle sizes measured with repeated SSIS scans of NanoSilica particles (30 nm nominal; blue symbols) and PSL spheres (30, 40, 50 nm nominal; yellow symbols) deposited on a silicon wafer.



of TSI Incorporated.

MSP - Visit our website www.tsi.com/msp for more information.

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